PATENT

NOTHE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application

Marc S. Weinberg, et al.

Application No.

08/841,224

Filed

April 29, 1997

For

TRENCHES TO REDUCE CHARGING EFFECTS AND

CONTROL OUT-OF-PLANE SENSITIVITIES IN TUNINO

FORK GYROSCOPES AND OTHER SENSORS

Examiner

R. Moller

Attorney's Docket

CSDL1-490XX

Group Art Unit:

2856

Bv:

Beverly E Mjorth

Registration No. 32,033 Attorney for Applicant(s)

AMENDMENT

RÉCÉIVÉD

FEB 03 1999

Assistant Commissioner for Patents Washington, D.C. 20231

GROUP 2100

Sir:

In response to the Office Action dated September 28, 1998, please amend the above identified patent application as follows:

In the Specification:

Please amend the specification as follows:

On page 9, line 10, after "etching." insert the following sentence:

-- The trench may also be formed by reactive ion etching, chlorine etching, SF_6 etching, or anisotropic etching. --

02/03/1999 ANOHANNE 00000001 08841224

02 FC:202

39.00 DP

- 1 -